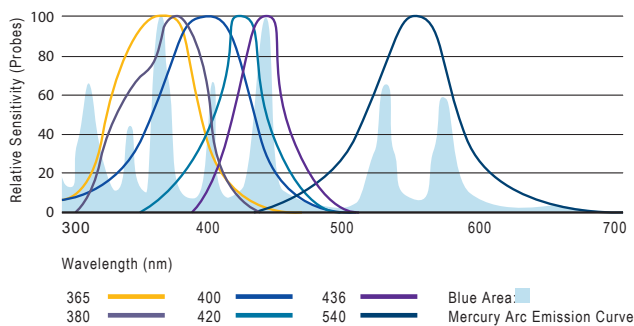


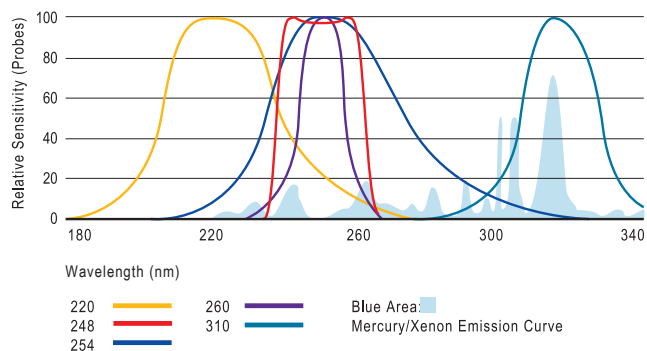
PHOTOLITHOGRAPHY UV LIGHT INTENSITY & ENERGY METERS

Model	317	356	357/457	358/458	459
Intensity Range (mw/cm ²)	16-1600	0.1-400	16-1600	40-4000	up to 6000
Energy Range (mJ/cm ²)	0-9999	0-9999	0-9999	0-9999	0-9999
Time Range (seconds)	0-9999	0-9999	0-9999	0-9999	0-9999
Wavelength (nm) (other wavelengths available)	310, 365 380, 400, 436	220, 254 260, 310, 365, 380, 400, 420, 436, 540	365, 400 420, 436	365, 400 420, 436	365, 400 420, 436
Accuracy	± 3	± 3	± 3.0 (WB) ± 1.5 (NB)	± 3.0 (WB) ± 1.5 (NB)	± 3%
Linearity (%)	2	2	2	2	2
Used for:	Projection Aligners	All Mask Aligners	Standard ASML, Nikon GCA, Canon, Rudolph Technology Steppers	High Intensity Steppers	Extreme High Intensity Ultratech Steppers
Calculations	Average energy; Percent deviation in energy, intensity and time for up to nine channels				
I/O	Print, Channel Select, Enable, Probe, Wavelength Check				
Power	110/220 VAC, 50/60 Hz, Rechargeable 6v Battery (with automatic shut off)				
Dimensions	(centimeter) 30.5 W x 12.7 H x 22.9 D • (inches) 12.0 W x 5.0 H x 9.0 D				
Weight	Approximately 3.6 kg (8.0 lbs)				

Near UV Probe Responses



Deep UV Probe Responses



*Narrow Band 365 and 436 nm probes are available calibrated with a 10nm bandwidth source.



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PHOTOLITHOGRAPHY UV LIGHT INTENSITY & ENERGY METERS



USED FOR:

PROJECTION ALIGNERS

CONTACT MASK ALIGNERS

WAFER STEPPERS

HIGH INTENSITY WAFER STEPPERS

For the past 40 years, OAI is the leader in precise repeatable measurement of UV light intensity and energy for critical applications. The Semiconductor, MEMS, Wafer Packaging, and Wafer Bumping Industries depend on OAI's reliable accurate instruments to control their UV photolithography processes.

FEATURES

- Averages up to nine exposure readings
- Measurement traceable to NIST
- Measures intensity, time and energy
- Records % deviation over a series of exposures
- RS 232 output enables the user to download and record analyzer measurement results (Model 457, 458, 459)
- Calibrated interchangeable probes
- Detachable probes enable user to match the spectral response of many photoresists
- Freeze display readings
- Displays probe wavelength to prevent set up errors
- Simple, push button operation for reliable results
- Rugged aluminum case features handle and probe pouch for portability

MODELS

MODEL 317 Projection Aligners

MODEL 356 Contact Mask Aligners

MODEL 357/457 All Standard Wafer Steppers: ASML, GCA, Nikon, Canon, & Rudolph Technologies Steppers

MODEL 358/458 All High Intensity Wafer Steppers: ASML, Nikon, Canon, Ultratech & Rudolph Technologies

MODEL 459 Ultratech Highest Intensity Wafer Steppers

